

Sir:

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:	)
Toshiya KOTANI et al.	)
Application No.: 09/748,227	) ) ) Group Art Unit: 2625
Filed: December 27, 2000	) ) Examiner: Kanjibhai B. Patel
For: MASK PATTERN CORRECTION METHOD, MASK PATTERN CREATION SYSTEM USING THE CORRECTION METHOD, AND COMPUTER-READABLE RECORDING MEDIUM	RECEIVED  JUL 1 4 2004
Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450	Technology Center 2600

## <u>AMENDMENT</u>

In reply to the March 9, 2004 Office Action, the period for response having been extended to July 9, 2004, by a request for extension of one month and fee payment filed concurrently herewith, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims in this paper.

Remarks follow the amendment sections of this paper.